

Semiconductor Device Processing (반도체 소자 공정 및 실습)

Lecture 2. Overview

Young Min Song

Assistant Professor

School of Electrical Engineering and Computer Science

Gwangju Institute of Science and Technology

http://www.gist-foel.net

ymsong@gist.ac.kr, ymsong81@gmail.com

A207, 232655





'Real' Schedule

Weekly Course Schedule							
Calendar	Description	*Remarks					
1st week	Introduction/Semiconductor Process Overview	Lectures					
2nd week	Semiconductor Process Overview	Lectures					
3rd week	Growth of compound semiconductors – MBE & MOCVD	Presentations					
4th week	Photolithography / Nanolithography	Presentations					
5th week	PECVD / Oxidation	Presentations					
6th week	Dry etching / Cleaning & Wet etching	Presentations					
7th week	Diffusion / Ion implantation	Presentations					
8th week	Mid-term Week	No midterm					
		1 to materin					
9th week	Metallization (Ohmic Contacts) / TLM measurement	Presentations					
9th week 10th week	Metallization (Ohmic Contacts) / TLM measurement						
		Presentations					
10th week	Metallization (Ohmic Contacts) / TLM measurement Fabrication & Measurement	Presentations Experiments					
10th week 11th week	Fabrication & Measurement	Presentations Experiments Experiments					
10th week 11th week 12th week		Presentations Experiments Experiments Experiments					
10th week 11th week 12th week 13th week	Fabrication & Measurement	Presentations Experiments Experiments Experiments Experiments Experiments					
10th week 11th week 12th week 13th week 14th week	Fabrication & Measurement	Presentations Experiments Experiments Experiments Experiments Experiments Experiments					



Detailed Schedule

MARCH 2017							
SUN	MON	TUE	WED	THU	FRI	SAT	
			1	Lect.	3	4	
5	6	Lect.	8	Lect,	10	11	
12	13	Lect.	15	<u>P1</u>	17	18	
19	(Mi	X . Segv	i ce) 22	P2 23	24	25	
26	27	P3 28	29	P4 30	31		

2017 MAY						
SUN	MON	TUE	WED	THU	FRI	SAT
	1	P11	3	P12	5	6
7	8	⁹ Exp	erime	nts	12	13
14	15	16 Exp	17 erime	¹⁸ nts	19	20
21	22	Exp	²⁴ erime	²⁵ nts	26	27
28	29		31. erime			

2017 APRIL							
SUN	MON	TUE	WED	THU	FRI	SAT	
						1	
2	3	⁴ <u>P5</u>	5	⁶ P6	7	8	
9	10	11 <u>P7</u>	12	13 P8	14	15	
16	17	18 X	19	20 X	21	22	
23	24	25 P9	26	27 P10	28	29	
30							

2017 JUNE							
SUN	MON	TUE	WED	THU	FRI	SAT	
				1	2	3	
4	5	⁶ Exp	7 erime	nts	9	10	
11	12	¹³ Fin	al Ex	¹⁵ am.	16	17	
18	19	20	21	22	23	24	
25	26	27	28	29	30		

www.free-printable-calendar.com

www.free-printable-calendar.com





Assessment and grading

Attendance (5%)

Presentations and pre-reports (30%)

- → 15 min presentation
- → Pre-report for 6 presentation topics (select one topic

per week, ~3 pages)

Final report (30%)

Final Exam (35%)



W수 사업 기술은 Gwangiu Institute of Science and Technology

Presentation Subjects

- 🧲 1. Molecular Beam Epitaxy (MBE) 송한성, 차수형
 - 2. Metal-Organic Chemical Vapor Deposition (MOCVD)) 이길주, 김현명
- 🚗 3. Photolithography 김현영, 노혜빈
 - 4. Nanolithography 유영진, 김무겸, 임지석
- 🥎 5. PECVD 박정환, 문승현
 - 6. Oxidation 김경필, 이제성
- ◢ 7. Dry etching 이혜지, 최병휘
 - 8. Cleaning / Wet etching 황진하, 김기영
- **z 9. Diffusion** 민경민, 이선규
 - 10. Ion implantation 이종헌, 석병탁
- 🚬 11. Metallization 김상민, 정준호
 - 12. Transmission Line Measurement (TLM) 장건태, 장재형





Contents

- 1. Semiconductors: introduction and history
- 2. Heterostructures: basic conception, history, materials, technologies
- 3. Device overview 1: LEDs
- 4. Device overview 2: Bio-integrated & Bio-inspired electronics



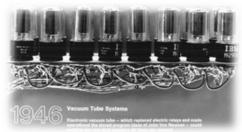


1940s



1st electronic general-purpose computer "Eniac"

- ➤ **Eniac** contains 17,468 vacuum tubes, weighed more than 30 tons, consumed 150 kW of electricity
- ➤ It could multiply two ten-digit numbers 40 times per second



Vacuum tubes

The fundamental building block of modern electronic device, "Transistor"

1947









- ➤ November 17, 1947 to December 23, 1947, <u>John Bardeen</u> and <u>Walter Brattain</u> at AT&T's Bell Labs in the US performed experiments. And solid-state group leader <u>William Shockley</u> saw the potential in this → **Transistor**
- > Small size, low electric consumption, and 10 times faster than Eniac





The Nobel Prize in Physics 1956

"for their researches on semiconductors and their discovery of the transtitor effect"



William Bradford
Shockley
1910–1989



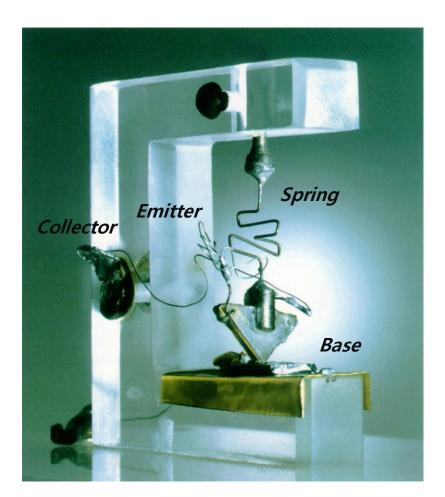
John **Bardeen**1908–1991



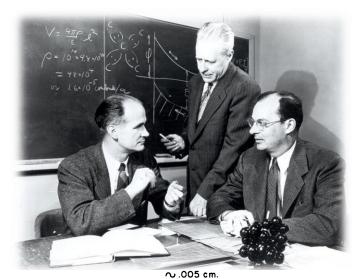
Walter Houser
Brattain
1902–1987

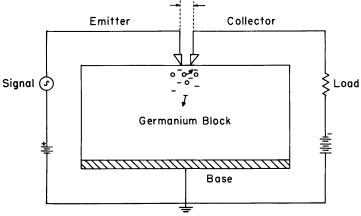






Bell telephone lab. Dec. 23, 1947



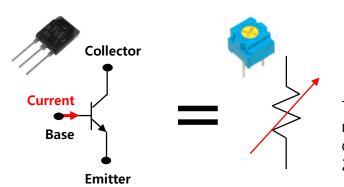


Schematic plot of the first "point-contact" transistor



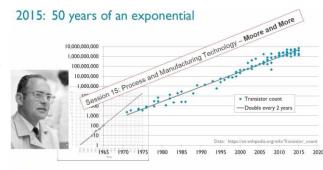


- <u>Transfer resister → Transistor</u>
- A small current at the base terminal can control or switch a much larger current between the collector and emitter terminals.





The Process Unit chip (PU chip) measures 678 mm² and consists of **3.99 billion transistors**, IBM, 2015.



➤ Transistor output is **5,700 times** larger than the wheat production by year

Transistor output in year : 10,000,000,000,000,000,000 = **2,700,000,000,000,000** / day





Wheat production by year: 703,000,000 t = **480,000,000,000** / day







1959

Development of semiconductor industry "MOSFET"





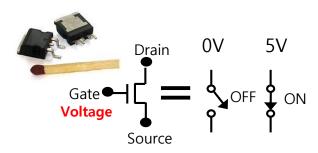


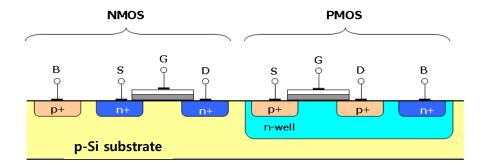
1960s



- > In 1959, Dawon Jahng and Martin M. Atalla at Bell Labs invented the MOSFET
- ▶ Integration of transistors at silicon substrate → circuit dimensions are reduced

> Role of turned-off switch by Gate voltage





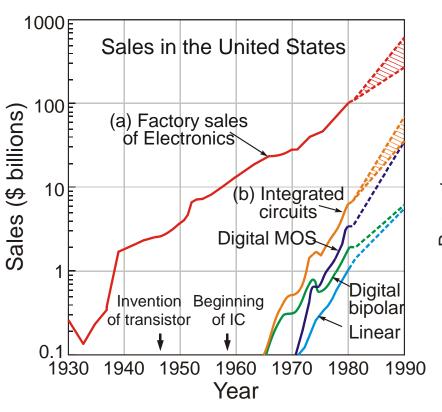
NMOS + PMOS (Complimentary MOSFET)

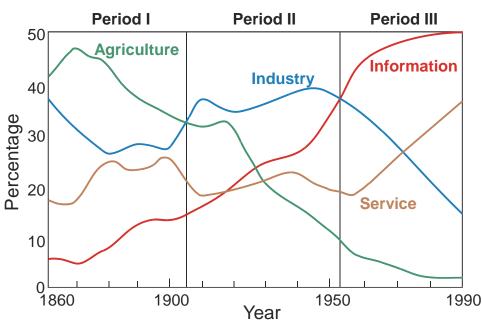
→ Method for large scale integration in the circuit



S. M. Sze, *J. Appl. Phys.* Vol. **22**, 1983

Factory sales of Electronics and IC





- Factory sales of Electronics in the United States over the past 50 years and projected to 1990
- Integrated circuit market in the United States



H. Iwai, H. wang, *Phys. World* Vol. **18**, 09, 2005

Moore's law I: device downsizing





10⁷nm

Vacuum tube

The first active electronic device to be invented was the vacuum tube

10⁶nm

The first Integrated circuit

Jack Kilby developed

the first integrated

circuit in 1958

10⁵nm

Size matters

Transistors in the first microprocessor (the Intel 4004) measured 10 µm

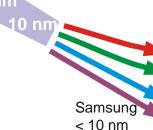
10⁴nm

How low can you go?

Further downsizing may not prove to be economically viable

Trade-off

Smaller devices suffer from larger leakage currents



1900 1950

1960

1970

1980

1990

2000

2010

2020

13



silicon transistor

in 1954

Small talk

The transistors in Intel's Pentium 4 processor are just 45 nm in size

10³nm

100 nm





H. Iwai, H. wang, *Phys. World* Vol. **18**, 09, 2005

Moore's law II: chip density



The road ahead

Further increase in chip density relies on new technologies

Intel Itanium

The world's most powerful chip can perform hundreds of millions of operations per second

10⁸

10⁹

Larger memory

Memory chips contain more transistors than processors



Gordon Moore Co-founder of Intel. who identified the trend for chip density 40 years ago

10⁷

Intel Pentium4

By 1995 the Pentium chip contained 42 million transistors

First microprocessor The Intel 4004

contained 2300 transistors

Intel Pentium

10⁶

The first Pentium processor contained 5.5 million transistors

1970 1980 1990 2000 2004 2010

2020





The Rise of Information and Communication Technology by "Light"

1963

Development of
Compound semiconductor laser

1966 Invention of optical fiber

1976 Development of 1.3 µm laser, fiber loss **(1dB/km)**

1979 Development of 1.55 μm laser, fiber loss (0.2dB/km)

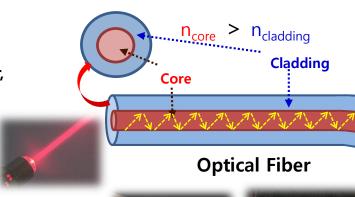
1980 Commercilization of optical communication

Commercilization of optical internet

Alferov Kroemer (The Nobel prize in physics, 2000)



Charles Kun Kao (The Nobel prize in physics, 2009)





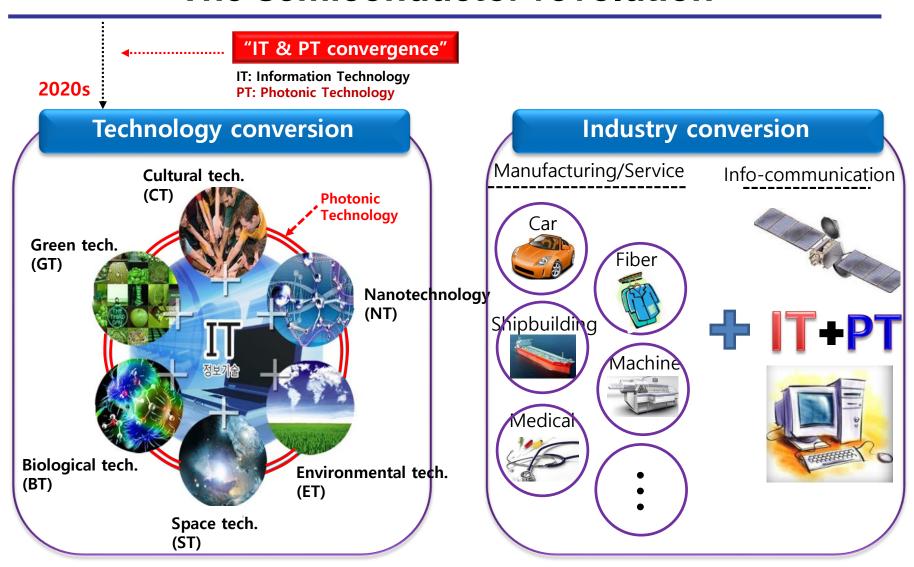
An **optical fiber** is a cylindrical dielectric waveguide that transmits light along its axis, by the process of **total internal reflection**.













Before heterostructure : quantum electronics

The Nobel Prize in Physics 1964

"for fundamental work in the field of quantum electronics, which has led to the construction of oscillators and amplifiers based on the maser-laser principle"



Charles Hard **Townes** b. 1915



Nicolay **Basov** 1922-2001



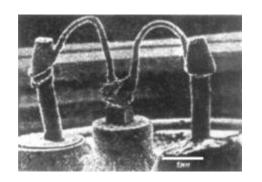
Aleksandr **Prokhorov** 1916–2002

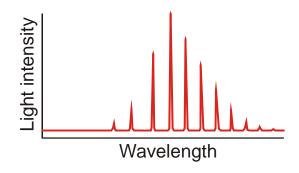


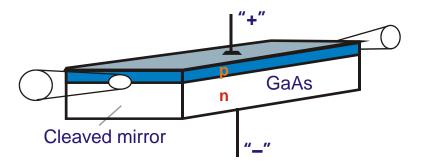


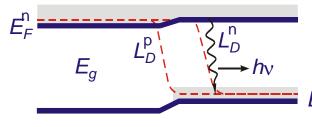
Before heterostructure : quantum electronics

- **January 1962:** observations of **superlumenscences** in GaAs p-n junctions (loffe Institute, USSR).
- Sept.-Dec. 1962: laser action in GaAs and GaAsP p-n junctions (General Electric, IBM (USA); Lebedev Institute (USSR).









Condition of optical gain:

$$E^{\mathsf{n}}_{\mathsf{F}} - E^{\mathsf{p}}_{\mathsf{F}} > E_{\mathsf{q}}$$





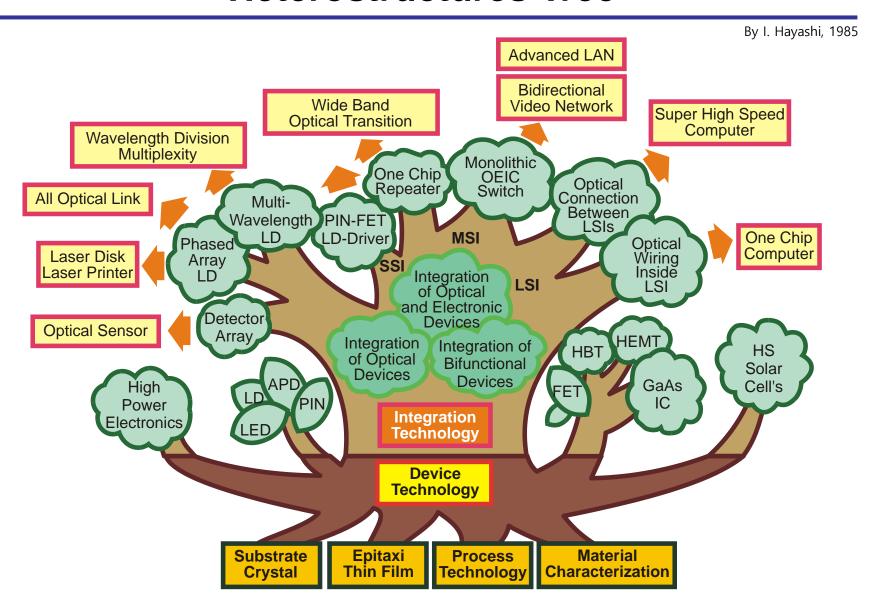
The impact of heterostructures

Z. Alferov, "Semiconductor Revolution in the 20th Century

- 1. Heterostructure a new kind of semiconductor materials:
- Expensive, complicated chemically & technologically but most efficient
- 2. Modern optoelectronics is based on heterostructure applications:
- Double heterostructure (DHS) laser key device of the modern optoelectronics
- Heterostructure (HS) PD the most efficient & high speed photo diode
- Optoelectronics integrated circuit (OEIC) only solve problem of high information density of optical communication system
- 3. Future high speed microelectronics will mostly use heterostructures
- 4. High temperature, high speed power electronics
- a new broad field of heterostructure applications
- 5. Heterostructures in solar energy conversion:
- The most expensive photocells and the cheapest solar electricity producer
- 6. In the 21st century heterostrucures in electronics will reserve only 1% for homojunctions



Heterostructures Tree

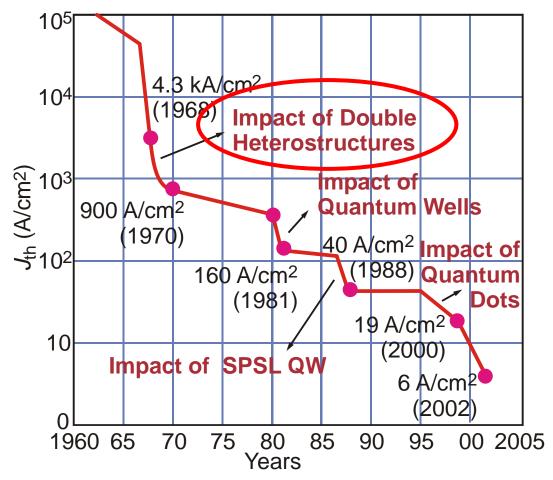




Year	Progress	Contributor
1963	Conception of double heterostructure lasers : double injection, confinement	Alferov, Kazarinov, Kroemer
1966 1967	GaAsP-lattice mismatched DH LDs, 77k AlGaAs-lattice matched heterostructures	Alferov et al. Rupprecht et al.
1969	AlGaAs- DH LD: J _{thr} =4300 A/cm ² , RT, pulse, 770 nm, LED, transistor, solar cell elements	Alferov et al.
1970	AlGaAs LDs, CW, RT, J _{thr} =940 A/cm ² InGaAsP : from IR to visible	Alferov et at., Hayashi, Panish, Alferov et al., Antipas et al.
1974	Quantum size effect in GaAs/AlGaAs (multi) graded structure	Dingle et al., Esaki, Chang, Tsu et al.
1975	First AlGaAs/GaAs MQW optically pumped laser, T=15k, hv=1.53 eV	Van der Ziel, Dingle et al.
1978	AlGaAs/GaAs LD, RT, QUANTUM WELL (QW) $J_{thr}=3x10^3$ A/cm ² , $\lambda=800$ – 840 nm	Dupius, Dapcus, Holonyak et al.
1980	QW heterostuctures: transistors, Quantum Hall effect	Mimura et al., Klitzing et al.
1982	AlGaAs/GaAs GRINSH, J _{thr} =160 A/cm ²	Tsang et al.
1983	GaAs/InGaAs strained LD, RT, CW	Holonyak et al.
1996 1997	InGaAs/GaAs QDs LDs, RT, CW J _{thr} =97 A/cm ² , P=160 mW, hv=1.3 eV	Bimberg, Park, Alferov et al.
2000	InGaAs/GaAs QD transverse&VCSEL, λ =1.3 μ m, J<100 A/cm², P=2.7 W	Ustinov et al.
1994 2000	Quantum engineering Quantum cascade lasers: λ =4 – 11 μ m, T=320k	Faist, Capasso, Sirtory, Cho
2000	Nobel Prize → "For developing semiconductor Heterostructures used in high-speed- and opto-electronics"	Zhores I. Alferov, Herbert Kroemer



Milestones of semiconductor lasers



- Evolution and revolutionary changes
- Reduction of dimensionality results in improvements



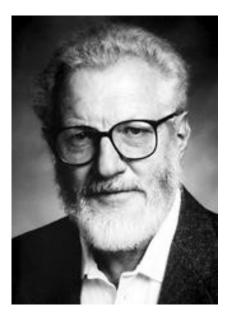
The Nobel Prize in Physics 2000

"for basic work on information and communication technology"

"for developing semiconductor heterostructures used in **high-speed- and opto-electronics**"

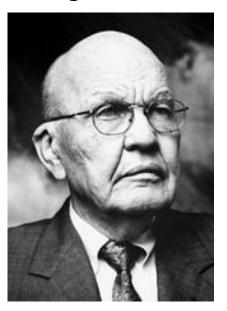


Zhores I. **Alferov** b. 1930



Herbert **Kroemer** b. 1928

"for his part in the invention of the integrated circuit"



Jack S. **Kilby** 1923–2005



THE NOBEL PRIZE IN PHYSICS

Speech by Professor Tord Claeson of the Royal Swedish Academy of Sciences.

... IT is viewed as a prime mover in the economic upswing our society has experienced over the past decade.

This year's Nobel Prize in Physics rewards contributions to the early developments of microelectronics and photonics, focusing on the integrated circuit, or "chip," as well as semiconductor heterostructures for lasers and high-speed transistors. ...

Semiconductor heterostructures can be regarded as laboratories of two-dimensional electron gases. The 1985 and 1998 Nobel Prizes in Physics for quantum Hall effects were based on such confined geometries. They can be reduced further to form one-dimensional quantum channels and zero-dimensional quantum dots for future studies. . . .



Some basic definitions of heterostructures

Heterostructures:

 Crystal consisted of one or more junctions between different semiconductors with different E_g, lattice constats, layer thickness

❖ Design:

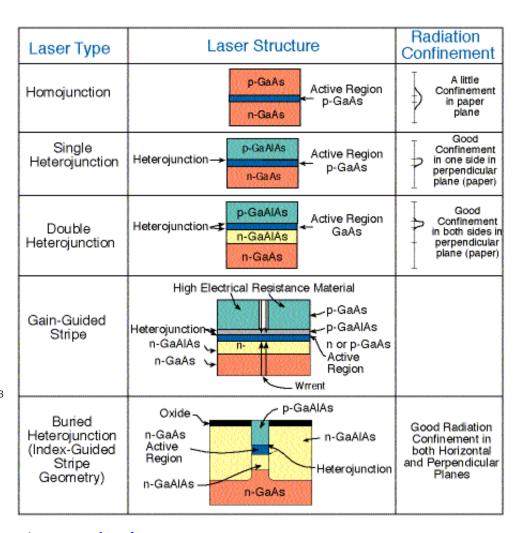
Subsrate + a sequence of thin layers

❖ Potential well:

- Active layer E_g^a < E_g^c of claddings (barriers)
- $\underline{L_x}^a << \underline{L_y}$, $\underline{L_z}$ and $\underline{L_x}^a >> \lambda_{\underline{B}}$ and $\underline{a_B}$ ($\lambda_{\underline{B}}$ Is the de Broglie wavelength of the carriers, $\underline{a_B}$ is the Bohr exciton radius)

Quantum well:

- $\underline{L_x}^a << \underline{L_y}$ $\underline{L_z}$ and $\underline{L_x}^a \sim \lambda_{\underline{B}}$ and $\underline{a_{\underline{B}}}$
- The carrier movement in the x direction is quantized.
- The carrier energy becomes definte discrete.
 - \rightarrow Optical and carrier confinement due to ΔE_{α} and Δn_{r}

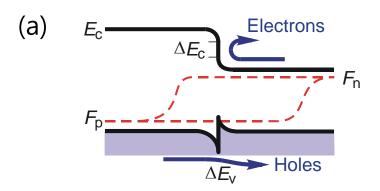






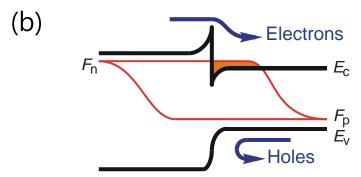
Classical heterostructures

Fundamental physical phenomena in classical heterostructures



One-side Injection

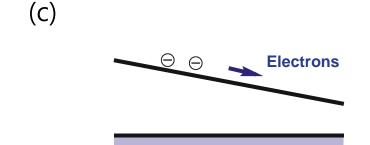
Proposal — 1948 (W. Shokley)
Experiment — 1965 (Zh. Alferov *et al.*)



Superinjection

Theory — 1966 (Zh. Alferov *et al.*)

Experiment — 1968 (Zh. Alferov *et al.*)



Diffusion in built-in quasielectric field

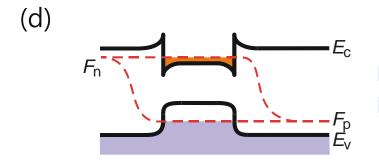
Theory — 1956 (H. Kroemer)

Experiment — 1967 (Zh. Alferov *et al.*)





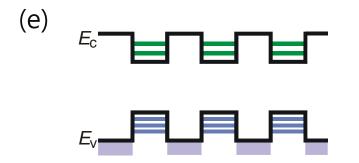
Classical heterostructures



Electrical and optical confinement

Proposal — 1963 (Zh. Alferov *et al.*)

Experiment — 1968 (Zh. Alferov *et al.*)



Superlattices and quantum wells

Theory — 1962 (L.V. Keldysh)

First experiment — 1970 (L. Esaki *et al.*)

Resonant tunnelling — 1963 (L.V. logansen)

In Quantum Wells — 1974 (L. Esaki *et al.*)

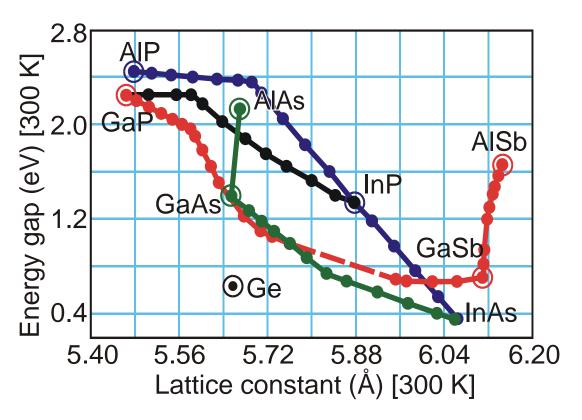
- Lattice-matched structures are necessary
- For lattice matching, multicomponent solid solution should be used
- In principle, epitaxial growth technology is necessary



Heterostructures – a new kind of semiconductor materials

Long journey from infinite interface recombination to ideal heterojunction

Lattice matched heterostructures



- **Ge–GaAs–1959** (R. L. Anderson)
- AlGaAs-1967 (Zh. Alferov *et al.*, J. M. Woodall & H. S. Rupprecht)
- Quaternary HS (InGaAsP & AlGaAsSb)

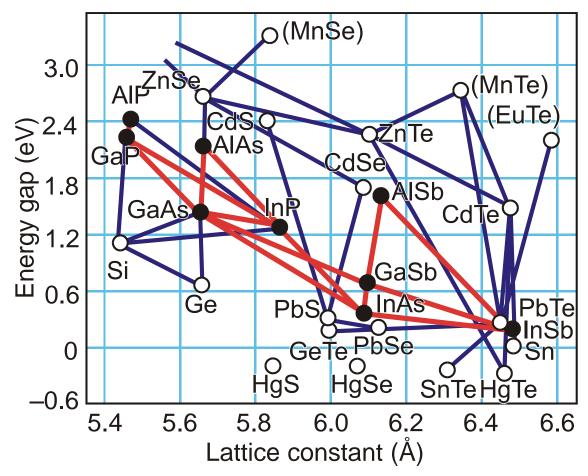
Proposal-1970

(Zh. Alferov *et al*.)

First experiment–1972 (Antipas *et al.*)



Heterostructures – a new kind of semiconductor materials



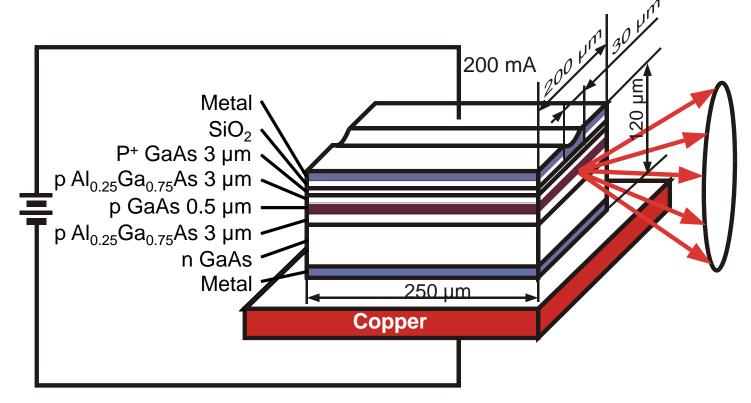
- Energy gaps vs. lattice constants for semiconductor IV elements, III-V and II(V)-VI compounds and magnetic materials in parentheses.
- Lines connecting the semiconductors, red for III-V, and blue for others, indicate quantum heterostructures, that have been investigated.





Heterostructures – DHS laser

Schematic representation of the DHS injection laser in the first CW-operation at room temper ature



- Fundamental need for structures with well-matched lattice parameters
- The use of multicomponent solid solutions to match the lattice parameters
- Fundamental need for epitaxial growth techniques

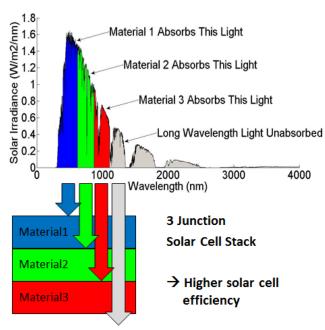


Heterostructures – space solar cell

Heterostructure solar cells



 Space station "Mir" equipped with heterostructure solar cells

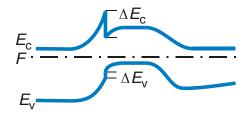


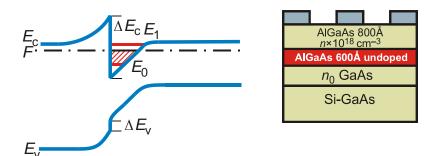
- Multi-junction solar cell
 Next-generation multijunction solar cells comprise multiple individual solar cells grown on top of each other
- → they can absord a wider range of the sun spectrum



Heterostructures – microelectronics

Heterojunction Bipolar Transistor

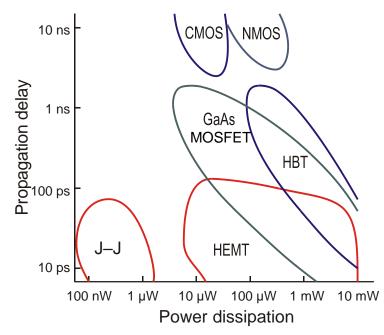




n AlGaAs-n GaAs Heterojunction

Suggestion—1948 (W.Shockley)
Theory—1957 (H.Kroemer)
Experiment—1972 (Zh.Alferov *et al.*)
AlGaAs HBT

HEMT—1980 (T.Mimura et al.)

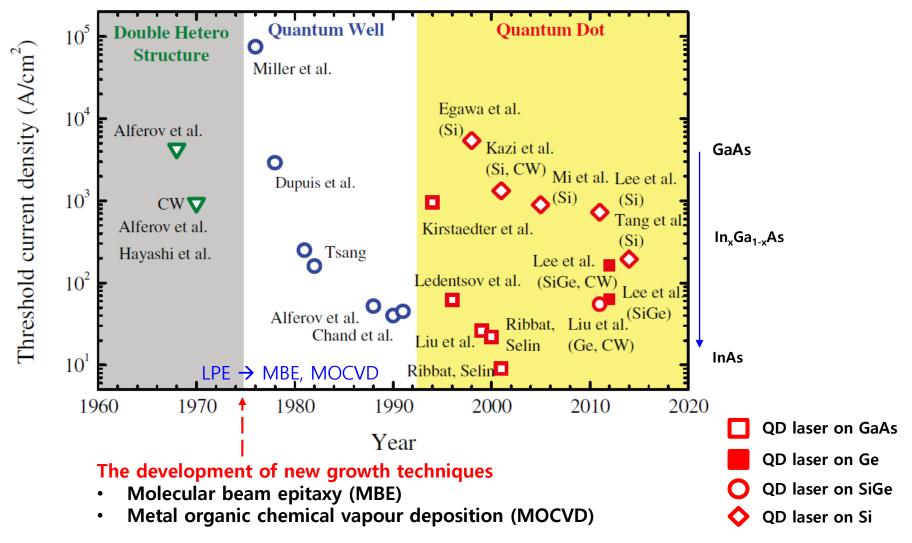


Speed-power performances



The evolution of laser diode performance

J. Phys. D: Appl. Phys. 48 (2015) 363001

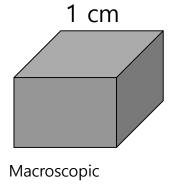


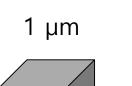
→ Enabled the crystal deposition to be controlled on an atomic scale





Quantum confined structures













Wavelength of light

de Broglie wavelength

Lattice constant

Volume semiconductor

Waveguide

Quantum size

Atom

de Broglie wavelength



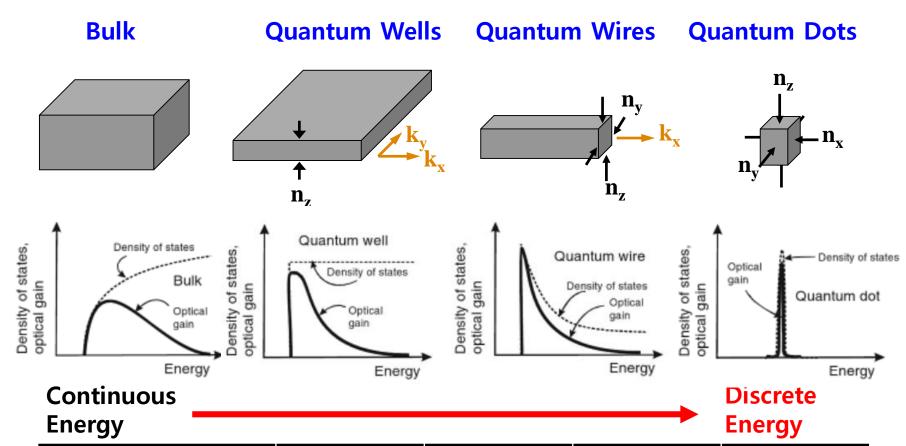
$$E = hv$$
$$mv^2 = h\frac{v}{\lambda}$$

$$\lambda = \frac{h}{mv} = \frac{h}{p}$$

- Size quantization effects can be already pronounced at a thickness ten to a hundred times larger than the lattice constant.
- An electron in GaAs, λ~24 nm, this implies that we need structures of thickness ~ 10 nm in order to observe quantumconfinement effects.



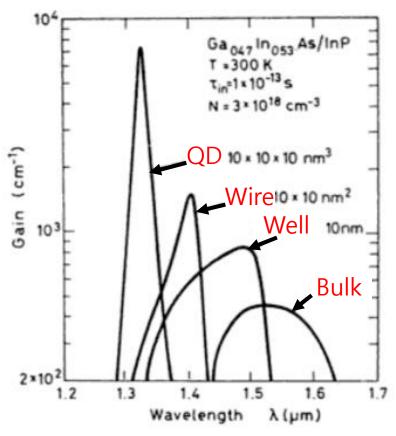
Quantum confined structures



Structure	Bulk	Quantum wells	Quantum wires	Quantum Dots
Quantum confinement	none	1D	2D	3D
Free dimensions	3D	2D	1D	0D



Quantum confined structures



Calculated material gain in $Ga_{0.47}In_{0.51}As/InP$ system Same electron injection (N=3 x 10^{18} cm⁻³)

The **peak gain increases** on going from bulk to QD. However, **gain bandwidth decrease** from bulk to QD.



Questions or comments?